

Version with markings to show changes made

IN THE SPECIFICATION:

Please amend the specification as follows:

Page 6, third paragraph:

-- Fig. 2B depicts a rear view of the flux dispenser 22 shown in Fig. 2A. As depicted, the flux dispenser 22 is further equipped with a main air pressure supply [26] 29, which maintains the main pressure of the flux dispenser 22 at a pressure range between about 60 psi and about 100 psi, thereby maintaining the fluid pressure and the valve pressure at the prescribed pressure ranges. A power supply line 27 and an interface port 28 are also provided to the flux dispenser 22. Particularly, the interface port 28 is provided for exchanging flux dispensing control data with a data processing device, e.g., a workstation 25 in Fig. 2A. For example, one can transform a specific fluid pressure and valve pressure corresponding to a certain configuration of the substrate 26 to computer-recognizable data, and save this data in the workstation 25. By using an input device, e.g., keyboard or mouse, to recognize a particular configuration of the substrate 26 to be processed, the workstation 25 generates a control command for the flux dispenser 22 to select a predetermined valve pressure or fluid pressure, thereby reducing the processing time and increasing the accuracy of the flux dispensing process.--

IN THE CLAIMS:

Please cancel claims 19-21 in their entirety without prejudice or disclaimer of the subject matter and amend claims 18, 22 and 26 as follows:

18. (Amended) An apparatus for dispensing flux on a substrate having a plurality of conductive terminals thereon, the apparatus comprising:

a data processing device adapted for determining an optimum valve pressure, flux viscosity, and flux spray pattern based on a configuration of the substrate and an arrangement pattern of conductive terminals thereon

[a flux fluid chamber containing flux having a viscosity range between about 10 centipoises and about 150 centipoises]; and

a flux dispense nozzle [connected to the flux fluid and] configured for spraying [the] flux at a valve pressure range between about 1.5 psi and about 30 psi to deposit the flux on the plurality of conductive terminals, wherein

the data processing device controls movement of the flux dispense nozzle in at least two dimensions relative to the substrate.

22. (Amended) The apparatus of claim [21] 18, wherein the data processing device decides a plurality of subsets based on the configuration of the substrate and the arrangement pattern of conductive terminals thereon, each subset comprising a plurality of conductive terminals closely located to each other.

26. (Amended) The apparatus of claim 25, wherein the flux needle has a needle opening having a diameter range between about 5 microns and about 60 microns.